

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	71	Strang-Eric-J.in.	US-PGPUB; USPAT; EPO; DERWENT	OR	ON	2006/01/31 14:54
S3	0	plasma adj processing and Gunn adj diode adj ((voltage adj controlled adj oscillator) vco)	US-PGPUB; USPAT	OR	ON	2006/01/31 16:41
S4	3	Gunn adj diode adj ((voltage adj controlled adj oscillator) vco)	US-PGPUB; USPAT	OR	ON	2006/01/31 16:36
S5	0	plasma adj processing and Gunn adj diode adj ((voltage adj controlled adj oscillator) vco)	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 16:40
S6	4	Gunn adj diode adj ((voltage adj controlled adj oscillator) vco)	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 16:40
S7	8	plasma adj processing and Gunn adj diode with ((voltage adj controlled adj oscillator) vco)	US-PGPUB; USPAT	OR	ON	2006/01/31 16:56
S8	8	plasma adj processing and Gunn adj diode with ((voltage adj controlled with oscillator) vco)	US-PGPUB; USPAT	OR	ON	2006/01/31 16:57
S9	8	plasma adj processing and Gunn adj diode with ((voltage adj controlled with oscillator) vco)	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 16:57
S10	97	Gunn adj diode with ((voltage adj controlled with oscillator) vco)	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 18:06
S14	50	((plasma adj processing) (electron adj density)) and semiconductor and diagnostic and resonator	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 19:28
S17	120	((plasma adj processing) (electron adj density)) and semiconductor and resonator and oscillator	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 19:44
S20	53	((plasma electron) adj density and control).ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/01/31 19:49
S21	116	((plasma electron) adj density and (measure measuring measurement)).ti.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/01 11:28
S22	622	(702/57).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 12:30
S23	483	(702/64).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 12:45
S24	366	(702/65).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 12:55

S25	250	(702/67).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 12:59
S26	92	(702/68).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 13:01
S27	289	(702/107).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 13:01
S28	1116	(702/182).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/02/01 13:19
S29	920	(702/183).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/02/01 13:34
S30	850	(702/188).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/02/01 15:24
S31	1446	(700/121).CCLS.	US-PGPUB; USPAT	OR	OFF	2006/02/01 16:16
S32	482	(324/464).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 17:34
S33	170	(324/633).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 17:36
S34	301	(324/636).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 17:40
S35	112	(324/76.76).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 17:44
S36	624	(324/76.39).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 19:15
S37	395	(438/5).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 19:28
S38	238	(438/8).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 19:35
S39	287	(438/9).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/01 19:54
S40	648	(438/10).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/02 11:45

S41	6345	(438/14,16,17).CCLS.	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	OFF	2006/02/02 11:45
S42	60	S41 and (plasma electron) adj density	US-PGPUB; USPAT	OR	ON	2006/02/02 11:50
S43	130	S41 and plasma adj processing	US-PGPUB; USPAT	OR	ON	2006/02/02 11:50
S46	133	((plasma adj processing) ((plasma electron) adj density)) and diagnostic adj system	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 16:14
S47	5	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with diode adj voltage	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 16:17
S48	14	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with Gunn adj diode	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 16:19
S49	34	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with (voltage current) adj monitor	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 17:23
S51	159	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with detector with voltage	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 17:49
S52	12	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with varactor	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 17:51
S53	5	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with voltage near sweep	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 17:59
S54	5	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) with resonance adj lock-on	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:13
S55	0	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) and (adjust adjusting adjusted change changing changed) with varactor near voltage	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:03
S56	0	((plasma adj processing) ((plasma electron) adj density)) and (control controller controlling controlled) and (modify modifying modified) with varactor near voltage	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:04
S57	13	((plasma adj processing) ((plasma electron) adj density)) and multi-modal adj resonator	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:14
S58	13	multi-modal adj resonator	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:14

S59	6	((plasma adj processing) ((plasma electron) adj density)) and sweep adj generator	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:31
S61	46	((plasma adj processing) ((plasma electron) adj density)) and default adj settings	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/02 18:35
S62	153	((plasma adj processing) ((plasma electron) adj density)) and default adj parameters	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 10:54
S63	1	2002-048950.NRAN.	DERWENT	OR	ON	2006/02/02 18:50
S64	1	2002-121749.NRAN.	DERWENT	OR	ON	2006/02/02 18:51
S66	0	((plasma adj processing) ((plasma electron) adj density)) and display with diode adj (voltage current)	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 10:55
S67	1	((plasma adj processing) ((plasma electron) adj density)) and display with (varactor detector) adj voltage	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 10:55
S68	19	((plasma adj processing) ((plasma electron) adj density)) and display with (voltage current) with (vco varactor detector)	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 10:57
S70	193	default with (save saved saving) with (directory location)	US-PGPUB; USPAT	OR	ON	2006/02/03 11:33
S72	0	((plasma adj processing) ((plasma electron) adj density)) and mode with (select selecting selected selection) with control with data adj acquisition	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 12:27
S73	0	((plasma adj processing) ((plasma electron) adj density)) and mode with (select selecting selected selection) with control with acquisition	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 12:27
S74	0	((plasma adj processing) ((plasma electron) adj density)) and mode with (select selecting selected selection) with calibration with acquisition	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 12:27
S75	51	((plasma adj processing) ((plasma electron) adj density)) and mode with (select selecting selected selection) with control	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 12:27
S76	2	varactor adj voltage with (electron plasma) adj density	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 13:52
S78	5	voltage with ((voltage adj controlled adj oscillator) vco) with (electron plasma) adj density	US-PGPUB; USPAT; EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2006/02/03 13:53